

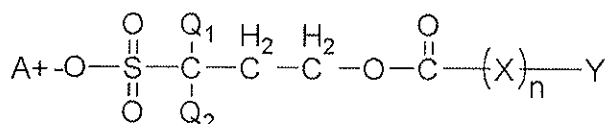
PHOTOACID GENERATOR, METHOD FOR MANUFACTURING THE SAME, AND
RESIST COMPOSITION COMPRISING THE SAME

ABSTRACT

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There are provided a photoacid generator, a method for manufacturing the same, and a resist composition comprising the same. The photoacid generator is a compound represented by the following formula 1:

[Formula 1]



10 wherein in the formula 1, Y represents any one selected from the group consisting of an alkyl group substituted with an aryl group, and an aromatic hydrocarbon group; Q₁ and Q₂ each independently represent a halogen atom; X represents any one selected from the group consisting of an alkanediyl, an alkenediyl, NR', S, O, CO and combinations thereof; R' represents any one selected from the group consisting of a hydrogen atom and an alkyl
15 group; n represents an integer from 0 to 5; and A⁺ represents an organic counterion.

The photoacid generator can produce, at the time of exposure, an acid which has a low diffusion rate, has a short diffusion distance, and exhibits an appropriate degree of acidity so that the line width roughness (LWR) characteristics can be improved, and elution of which in a solvent such as pure water that is used in the process can be
20 controlled.